

# Upgrading Wolter Imagers for X-Ray Diagnostics in the Z Pulsed-Power Facility at Sandia National Laboratories

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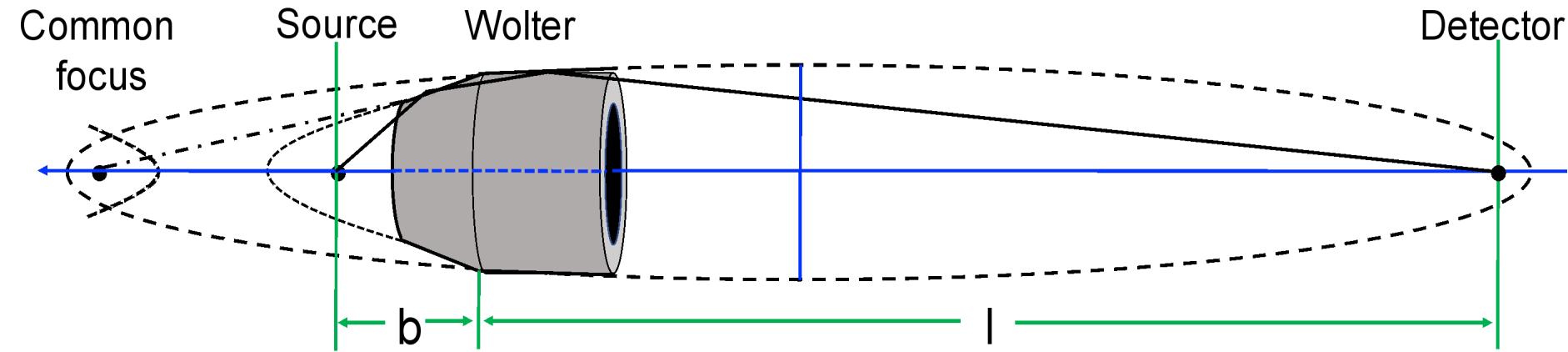
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# Operation Principle of Wolter Optics

- Three families of designs, nestable version (Wolter I) most widely used
- Wolter I has properties similar to a thin lens
- Wolter design addresses two challenges of grazing-incidence optics
  - Nested designs allow for increased collecting efficiency
  - Two conic surfaces of revolutions nearly satisfy Abbe sine rule reducing strongest aberration contributions



Major advantages of Wolters include:  
large solid angle, large field of view (FoV), large throughput



# Z-Wolter Optics Performance

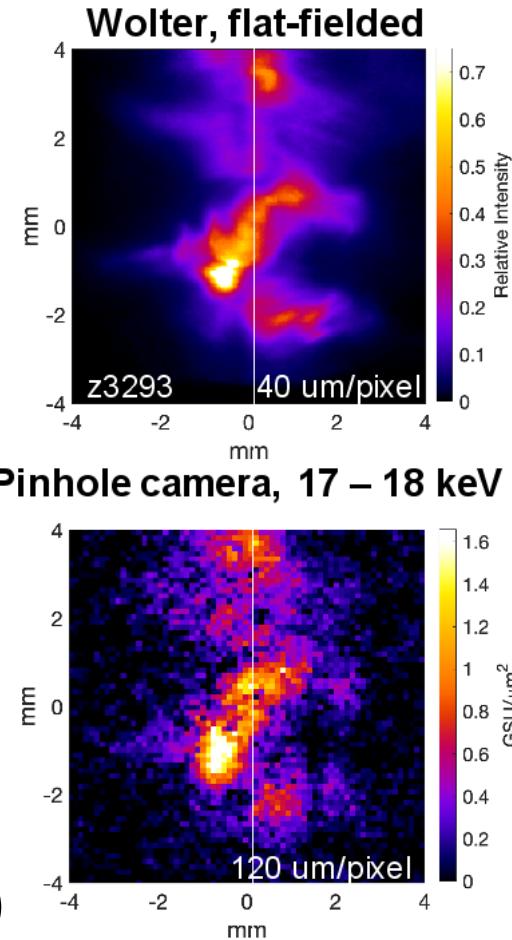
## Wolter imager successfully fielded in SNL's Z machine

- K-shell emission data using Mo wire arrays ( $\sim 17.5$  keV) demonstrated superior imaging capability over large field of view ( $5 \times 5 \text{ mm}^2$ ) enabling in-depth study of these sources
- Improvement in signal of factor 100-1000 compared to pinhole camera image in same E-range
- Wolter optic reveals features of order  $< 200 \text{ } \mu\text{m}$

## Extending Wolter applications for future experiments

- Temporally-resolved imaging (photon starvation)
- Higher energies (dimmer sources/need high reflectivity R)
- Better spatial resolution (challenges for optics fabrication)

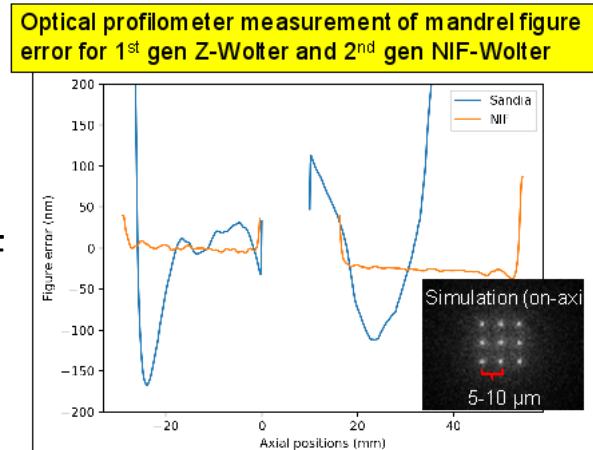
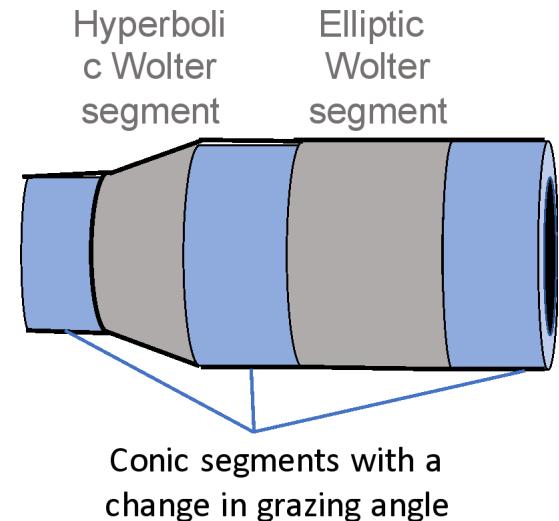
Next generation of Wolter imaging diagnostics requires high throughput and ideally further improved spatial resolution ( $< 50$  microns)



# Improvements for Next-Gen Wolter Optics

## 1) Fabrication of High-Precision Mandrel

- Design improvements for mandrels: flat segments added to mitigate performance-degrading end-effects
- Polishing procedure improved to produce more consistent surface: Upgraded polishing slurry & alignment procedure for sub-aperture polisher (Zeeko)
  - 2x decrease in figure error & reduced process time
- MSFC IXPE (Imaging X-ray Polarimetry Explorer) optic required improved lap polishing directly benefitting NIF/Z Wolter
  - Error introduced during polishing reduced by a factor of ~5 with new process
- Improvements enabled fabrication of test mandrel meeting NIF figure requirement to achieve  $<5\text{-}10 \mu\text{m}$  resolution over 1 mm FoV (10x reduction in figure error)

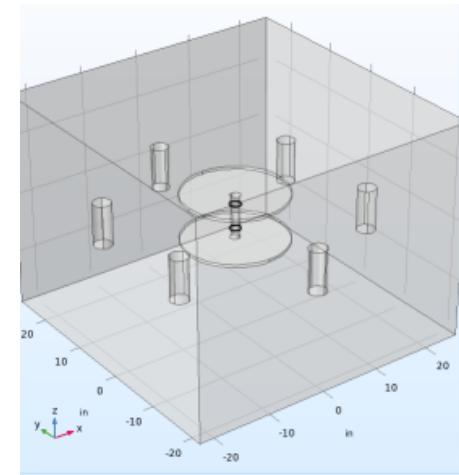


Improved Lap polishing and Zeeko able to maintain figure and roughness to provide mandrel expected to produce shells for  $<50 \mu\text{m}$  spatial resolution on Z

# Improvements for Next-Gen Wolter Optics

## 2) Advancing Replication Technology

- Improved fast (<1h/shell) metrology setup using IXPE assembly station
  - Shells suspended from 3 wires
  - Enables measurements along length of shell and multiple azimuthal positions
  - First results indicate end-effect deformations restricted to flat pieces (4-8  $\mu\text{m}$  peak-to-valley); optic largely unaffected



- Comsol 3D simulations of replication bath to determine key factors to improve deposition uniformity
  - Geometric dimensions
  - Electrolyte conductivity
  - Gasket configuration and copper tape usage
- Replication tests planned to verify model predictions
- Plans to include effects causing non-symmetric azimuthal variations

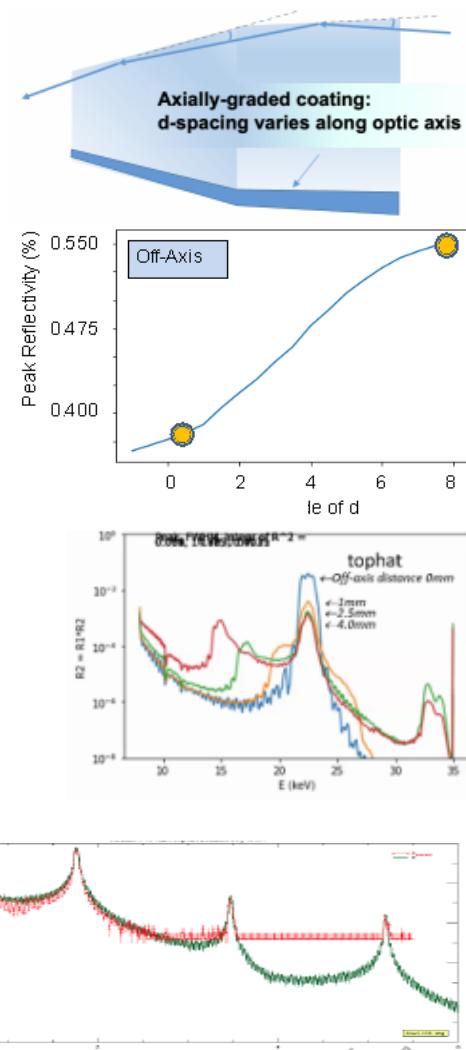
Focus on improving replication process to keep additional figure error contributions from replication and release small and use full potential of mandrel



# Improvements for Next-Gen Wolter Optics

## 3) Boosting Multilayer Reflectivity

- Optimization of multilayer (ML) recipes using evolved search algorithms for constant d-spacing, multiple-stack and depth-graded designs
  - Study showed axial ML grading of about 6% could further increase reflectivity by 1.4x
  - Optimization for best performance and maximal flexibility: highest reflectivity, flat response, optimal rejection of photons outside of spectral ROI (non-thermal vs thermal)
- Advancing multilayer deposition process
  - Push reflectivity by increasing number of deposited layer pairs via higher operating current of coater
  - Improvements to coating uniformity possible using coating mask
  - Exploring additional options to boost reflectivity
    - Use of alternative ML material systems
    - Reactive sputtering to increase R and reduce stress



# Conclusions and Outlook

- Wolter optics successfully employed in SNL's Z-machine:  
Improvement in signal-to-noise of factor  $\sim$ 10-30 compared to current best diagnostic and reached 60-300  $\mu\text{m}$  spatial resolution (previously 900  $\mu\text{m}$ )
- Pushing technologies to higher spatial resolutions (<50  $\mu\text{m}$  for Z, <5-10  $\mu\text{m}$  for NIF) with R&D on mandrel fabrication and polishing as well as replication
- Implementation of time-gated imaging has highest priority together with longer-term goal of pushing Wolter application towards higher energies both require boosting the reflectivity

For more information please attend Jeff Fein's invited talk:  
High-resolution imaging of warm x-ray sources with a Wolter optic on the Z Machine  
or feel free to contact me ([vogel9@llnl.gov](mailto:vogel9@llnl.gov))



# THANK YOU FOR YOUR ATTENTION! QUESTIONS?



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